

IN THE CLAIMS

Please amend the claims as follows:

1. (Currently Amended): A rinse solution nozzle assembly for dispensing a rinse solution on a substrate, comprising:

a first nozzle array including one nozzle disposed on a central axis extending normally from a center of the substrate, and configured to dispense said rinse solution substantially near the center of said substrate;

a first control valve coupled to said first nozzle array and configured to actuate a first flow rate of said rinse solution through said first nozzle array;

a second nozzle array including a plurality of nozzles, said nozzles arranged at fixed positions along a radial span aligned with the central axis and extending from near center of the substrate toward a perimeter of the substrate and configured to dispense said rinse solution across the radial span on a side of the substrate facing the first nozzle array;

a second control valve coupled to said second nozzle array and configured to actuate a second flow rate of said rinse solution through said second nozzle array; and

a fluid supply line connecting a rinse solution supply to both the first control valve and the second control valve and supplying the rinse fluid solution through the fluid supply line both to the first control valve and to the second control valve for supply of the same rinse solution to both the first nozzle array and the second nozzle array.

2. (Original): The rinse solution nozzle assembly as recited in claim 1, further comprising:

a controller coupled to said first control valve and said second control valve, configured to control said first flow rate through said first nozzle array, and configured to control said second flow rate through said second nozzle array.

3. (Previously Presented): The rinse solution nozzle assembly as recited in claim 1, further comprising:

a rinse solution supply system coupled to the fluid supply line.

4. (Original): The rinse solution nozzle assembly as recited in claim 3, wherein said rinse solution supply system comprises at least one of a fluid supply valve, a filter, a flow measurement device, and a flow control device.

Claims 5-6 (Canceled).

7. (Original): The rinse solution nozzle assembly as recited in claim 1, wherein said substrate is rotated during dispensing of said rinse solution.

8. (Original): The rinse solution nozzle assembly as recited in claim 1, wherein said rinse solution comprises de-ionized water.

9. (Original): The rinse solution nozzle assembly as recited in claim 2, wherein said controller is further configured to open said first control valve for a first period of time permitting a flow of the rinse solution through said first nozzle array.

10. (Original): The rinse solution nozzle assembly as recited in claim 9, wherein said controller is further configured to open said second control valve for a second period of time permitting a flow of the rinse solution through said first nozzle array and said second nozzle array following said first period of time.

11. (Currently Amended): A cleaning system for providing a rinse solution on a substrate, comprising:

a cleaning chamber;

a substrate holder coupled to said cleaning chamber and configured to support said substrate;

a drive unit coupled to said substrate holder and configured to rotate said substrate holder;

a rinse solution nozzle assembly coupled to said cleaning chamber and configured to dispense said rinse solution in said cleaning chamber;

said rinse solution nozzle assembly including,

a first nozzle array including one nozzle disposed on a central axis extending normally from a center of the substrate holder, and configured to dispense said rinse solution substantially near the center of said substrate,

a first control valve coupled to said first nozzle array and configured to actuate a first flow rate of said rinse solution through said first nozzle array,

a second nozzle array including a plurality of nozzles, said nozzles arranged at fixed positions along a radial span aligned with the central axis and extending from near center of the substrate toward a perimeter of the substrate and configured to dispense said rinse solution across the radial span on a side of the substrate facing the first nozzle array,

a second control valve coupled to said second nozzle array and configured to actuate a second flow rate of said rinse solution through said second nozzle array, and

a fluid supply line connecting a rinse solution supply to both the first control valve and the second control valve and supplying the rinse fluid solution both to the first control valve and to the second control valve for supply of the same rinse solution to both the first nozzle array and the second nozzle array; and

a controller coupled to said first control valve and said second control valve of said rinse solution nozzle assembly, configured to control said first flow rate through said first nozzle array, and configured to control said second flow rate through said second nozzle array.

12. (Original): The cleaning system as recited in claim 11, wherein said controller is coupled to said drive unit and configured to control at least one of a rotation rate and a rotation rate acceleration of said drive unit.

13-25 (Canceled).

26. (Currently Amended): A system for providing a rinse solution on a substrate, comprising:

means for supporting the substrate in a chamber;

means for rotating the substrate;

means for dispensing a rinse solution on a central axis disposed on a central axis extending normally from a center of the substrate in a first step to neutralize the surface of the substrate and a second step to provide hydraulic pressure from said rinse solution substantially along the entire surface of the substrate on a same side of the substrate as in the first step, and

said means for dispensing including a fluid supply line connecting a rinse solution supply to both the first control valve and the second control valve and supplying the same rinse fluid solution both separately to the center of the substrate and along the entire surface of the substrate by nozzles arranged at fixed positions along a radial span aligned with the central axis and extending from near center of the substrate toward a perimeter of the substrate.

27. (Canceled).